

Fabrication & Evaluation of Nanostructured Thermoelectrics

Generate Renewable Energy Efficiently using Nanofabricated Silicon (GREEN Silicon)



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Semiconductor Device Group

Si Photonics

Si thermal photovoltaics Miniature cold atom systems

MEMS gravimeters





Engineering and Physical Sciences Research Counci





Science & Technology Facilities Council





Ge MIR Plasmonics

Si SETs & **Electrometers**





Ge SPADs & Si Quantum **Photonics**

SiGe Thermoelectrics



Bulk Thermoelectric Materials Performance



Nature Materials 7, 105 (2008)



- Bulk n-Bi₂Te₃ and p-Sb₂Te₃ used in most commercial thermoelectrics & Peltier coolers
- But tellurium is 9th rarest element on earth !!!



Bulk Si_{1-x}Ge_x (x~0.2 to 0.3) used for high temperature satellite applications



ZT versus Temperature

p-type

n-type



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Nanostructures can improve Seebeck coefficient and/or decrease thermal conductivity



Increase α through enhanced DOS:



 $-\alpha$ increasing \longrightarrow

M. Cutler & N.F. Mott, Phys. Rev. 181, 1336 (1969)





Key wavelengths for scattering phonons 1.2 to 4 nm



Superlattice Designs: 4.5 µm Thick

Design 1	Design 2	Design 3	Design 4
80 nm n-Ge	80 nm n-Ge	80 nm n-Ge	80 nm n-Ge
1.55 nm n-Si _{0.22} Ge _{0.78}	2.3 nm n-Si _{0.3} Ge _{0.7}	1.8 nm n-Si _{0.3} Ge _{0.7}	1.5 nm n-Si _{0.3} Ge _{0.7}
		x178 repeats	x107 repeats
			15.5 nm n-Ge
x889 repeats	x336 repeats	9.3 nm n-Ge	1.5 nm n-Si _{0.3} Ge _{0.7}
4.64 nm n-Ge	12.2 nm n-Ge	1.8 nm n-Si _{0.3} Ge _{0.7}	16.0 nm n-Ge
1.55 nm n-Si _{0.22} Ge _{0.76}	2.3 nm n-Si _{0.3} Ge _{0.7}	9.3 nm n-Ge	2.0 nm n-Si _{0.3} Ge _{0.7}
		2.6 nm n-Si _{0.3} Ge _{0.7}	16.7 nm n-Ge
Augusta and a second		and the second se	2.8 nm n-Si _{0.3} Ge _{0.7}
Substrate	Substrate	Substrate	Substrate
4.64 nm n-Ge	12.2 nm n-Ge	9.3 nm n-Ge	16.7 nm n-Ge
5 nm graded n-SiGe	5 nm graded n-SiGe	5 nm graded n-SiGe	5 nm graded n-SiGe
1 μm n-Si _{0.083} Ge _{0.917}	1 μm n-Si _{0.05} Ge _{0.95}	1 μm n-Si _{0.032} Ge _{0.968}	1 μm n-Si _{0.032} Ge _{0.968}
y=0.917	y=0.95	y=0.968	y=0.968
13 μm graded Si _{1-y} Ge _y	13 μm graded Si _{1-y} Ge _y	13 μm graded Si _{t-y} Ge _y	13 μm graded Si _{1-γ} Ge _y
y=0.0	y=0.0	y=0.0	y=0.0
p [–] -Si (001)	p⁻-Si (001)	p⁻-Si (001)	p⁻-Si (001)



Narrow QW Superlattice Minibands



0

Only L-valley electrons form minibands











TEM of Single Barrier & 3 Barrier Material

Single barrier

Three barriers





n-type vertical Design 6 (8722)

3 barriers with wide Ge QWs





Vertical structure characterisation device





Comsol Thermal Parasitic Modelling





Cosmol Thermal Modelling





45 nm Wide n-Silicon Nanowires



10.0kV 12.5mm x1.80k SE(M) 2/20/13 16:11

30.0um



Bulk SiGe Material Design





LPCVD SiGe Wafer Growth

200 µm

ASM 2000E LPCVD system

200 mm SOITEC 55 nm Si, 155 nm box substrates

Slip planes

/ cracks



155

155 nm SiO₂

Si (001) substrate



Module Design: Heat Flow, Q





Simulation of Performance @ $T_H = 500$ °C





Operating temperature, T_H = 500 °C



Shorter legs better for high P but need to consider κ to maintain ΔT



Microfabricated Legs & Thermometers

68 pairs TE legs

16.00 kV

6.6 mm





Flip-Chip Bonding

In bumps











Final Module & Test







Heater & 2 Peltiers used to drive heat through module

Microfabricated thermometers measure ΔT





Material cracks limit yield & .. legs: requires better epitaxy (limited area epitaxy?)



In bumps limit T_H & dominate leg R



High temperature bumps & flip-chip bonding in development



Present silicides limited to ≤ 400 °C: new high T silicides e.g. TiSi₂ or WSi₂ stable to > 700 °C



Ohmic to bumps requires better diffusion barrier => TiN





Si/SiGe heterostructures for engineered electron & phonon transport towards enhanced thermoelectrics



New test structures for α and κ developed



ZT and power factor enhanced over bulk Si, Ge and SiGe values



Prototype modules delivered: optimisation required



http://www.greensilicon.eu/GREENSilicon/index.html



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